



I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to:

Commission for Patents
PO Box 1450
Alexandria, VA 22313-1450

On 5/10/03

TOWNSEND and TOWNSEND and CREW LLP

By: S. Kaines

PATENT
Attorney Docket No.: 16301T-034100US
Client Ref. No.:
004182/ETCH/DRIE/JB1

RECEIVED
MAY 15 2003
GROUP 1700

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Liang-Guo Wang et al.

Application No.: 09/767,282

Filed: January 22, 2001

For: RF POWER DELIVERY FOR
PLASMA PROCESSING USING
MODULATED POWER SIGNAL

Examiner: Parviz Hassanzadeh

Art Unit: 1763 #14A
AMENDMENT 5/16/03
mw

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Office Action mailed January 8, 2003, please amend the above-identified application as follows:

IN THE SPECIFICATION

Please replace the paragraph beginning at page 1, line 13 with the following paragraph.

--It is desirable to increase the number of controllable processing parameters in a plasma processing apparatus. More controllable process parameters provide process engineers with more ways to control the operation of the apparatus to optimize a given

A